



Inventor: Dan G. Custer et al.

Title: Polishing Systems, Method of Polishing Substrates, and Methods of Preparing Liquids for Semiconductor Fabrication Processes

Assignee: Micron Technology, Inc.

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the United States patents listed on the attached Form PTO-1449, and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: Oct 24, 2000

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